

	Hits	Search Text	DBs
31	66	(mask or pattern or photolithograph\$4 or ((resist or photoresist) near12 (mask or structure or pattern or pedestal))) and (((ion near9 mill\$4) or (ion near9 beam) or IBE or (ion near6 beam near9 source) or (ion near9 source) or (ion near9 (gun or module))) same (angle or tilt\$4 or rotat\$4 or spin\$4 or slop\$4) same (vary4 or different or adjust or chang\$4 or var\$4 or rang\$4 or oblique)) and ((rotat\$4 or mov\$3 or tilt\$4 or spin\$4) same (substrate or wafer)) and (shadow\$5 or undercut\$4 or overhang) and (((sidewall or side) near22 profile) or hyperbol\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
32	110	(mask or pattern or photolithograph\$4 or ((resist or photoresist) near12 (mask or structure or pattern or pedestal))) and (((ion near9 mill\$4) or (ion near9 beam) or IBE or (ion near6 beam near9 source) or (ion near9 source) or (ion near9 (gun or module))) same (angle or tilt\$4 or rotat\$4 or spin\$4 or slop\$4) same (vary4 or different or adjust or chang\$4 or var\$4 or rang\$4 or oblique)) and ((rotat\$4 or mov\$3 or tilt\$4 or spin\$4) same (substrate or wafer)) and (shadow\$5 or undercut\$4 or overhang) and ((pedestal or pattern or mask) same (first or second or different) same width)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB